AMENDMENTS TO THE CLAIMS

Claims 1 and 2 (canceled)

Claim 3 (currently amended): A substrate processing system comprising:

a plurality of first processing units that number N, each adapted to process a substrate by a first treatment with a first processing fluid, where N is a natural number not less than 3;

at least one second processing unit adapted to process the ~~substrate~~ substrates; and

a supply device adapted to generate the first processing fluid to be supplied to the first processing units, the supply device having a capacity of supplying the first processing fluid to only N-n of the first processing units simultaneously at respective supply rates, each supply rate complying ~~complies~~ with a demand for appropriately performing the first process in each of the N-n first processing units, where n is a natural number and N-n is not less than 2; and

a substrate conveyer adapted to convey the ~~substrate~~ substrates and to load and unload the ~~substrate~~ substrates into and from the first and second processing units; and

a controller that controls a timing of loading of the ~~substrate~~ substrates into the first processing units by the substrate conveyer so as to avoid a case where more than N-n of the first processing units are simultaneously carrying out the first treatment with each using the first processing fluid, ~~where n is a natural number and N-n is not less than 2~~

wherein the supply device is configured to generate the first processing fluid by converting at least one source fluid supplied to the supply device.

Claim 4 (original): The system according to claim 3, wherein the controller is configured to control the substrate conveyer so that the conveyer loads the substrates into the first processing units by turns at T/(N-n) intervals, where T is a time period necessary for carrying out the first treatment in each of the first processing units by using the first processing fluid.

Claim 5 (new): The system according to claim 3, further comprising a flow control device configured to adjust a flow rate of the at least one source fluid supplied to the supply device so that the supply device supplied the first processing fluid at a flow rate corresponding to a sum of the demand for appropriately performing the first process in each of the first processing units performing the first process simultaneously.

Claim 6 (new): The system according to claim 3, wherein the supply device is configured to generate the processing fluid from a first source fluid and a second source fluid.

Claim 7 (new): The system according to claim 6, further comprising a first flow control device and a second flow control device configured to adjust a flow rate of the first source fluid and the second source fluid supplied to the supply device, respectively, so that the supply device supplies the first processing fluid at a flow rate corresponding to a sum of the demand for appropriately performing the first process in each of the first processing units performing the first process simultaneously.

Claim 8 (new): The system according to claim 6, wherein the supply device is an ozone generator, the first source fluid is oxygen gas, and the second source fluid is nitrogen gas.

Claim 9 (new): The system according to claim 3, wherein each of the first processing units is an ozone processing unit configured to process a substrate with a mixed fluid containing the first processing fluid and water vapor, the first processing fluid being ozone gas, and wherein the second processing unit is a cleaning unit configured to clean the substrate having been processed by any one of the first processing unit.